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ABSTRACT OF THE DISCLOSURE

A chemical vapor deposition process for laying down a gallium oxide coating on a glass substrate through the use of an organic ester and an inorganic gallium halide. The organic ester preferably contains 3 - 6 carbon atoms which contributes to obtaining a high deposition rate. The chemical vapor deposition method to form the gallium 10 oxide coating is preferably at, essentially, atmospheric pressure. The resulting article has a gallium oxide coating which can be of substantial thickness because of the high deposition rates attainable. The coating deposition rates resulting from the method of the present invention are preferably greater than or equal to 75Å per second.